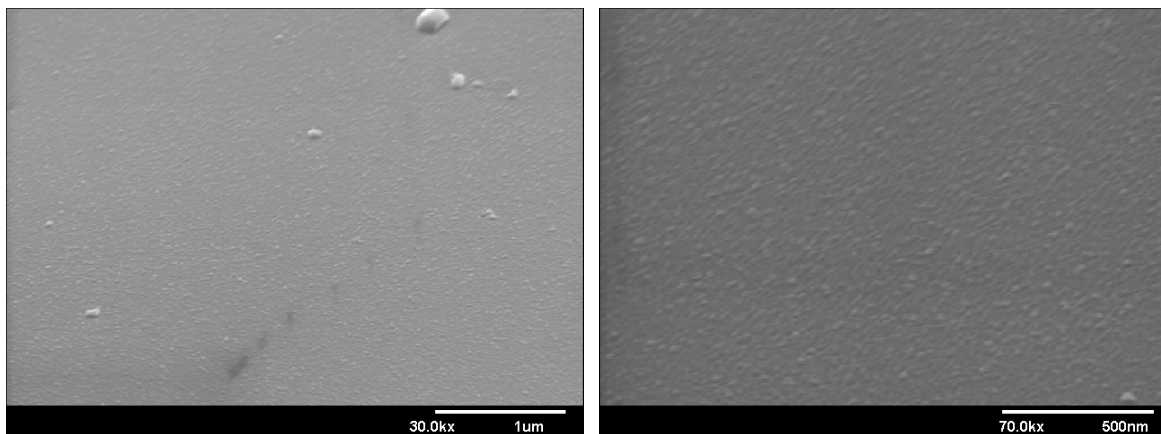
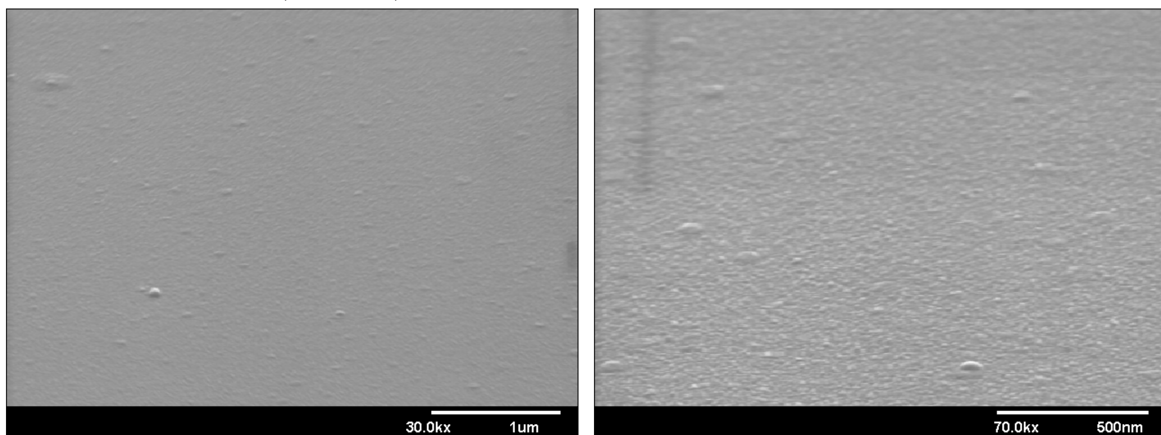
4-6 相同製程前處理之 SEM&AFM 圖面

A1、550℃ H_2:100 (Ni 1 nm)



A2、550℃ H_2:100 (Ni 5 nm)



A3、550℃ H_2:100 (Ni 7 nm)

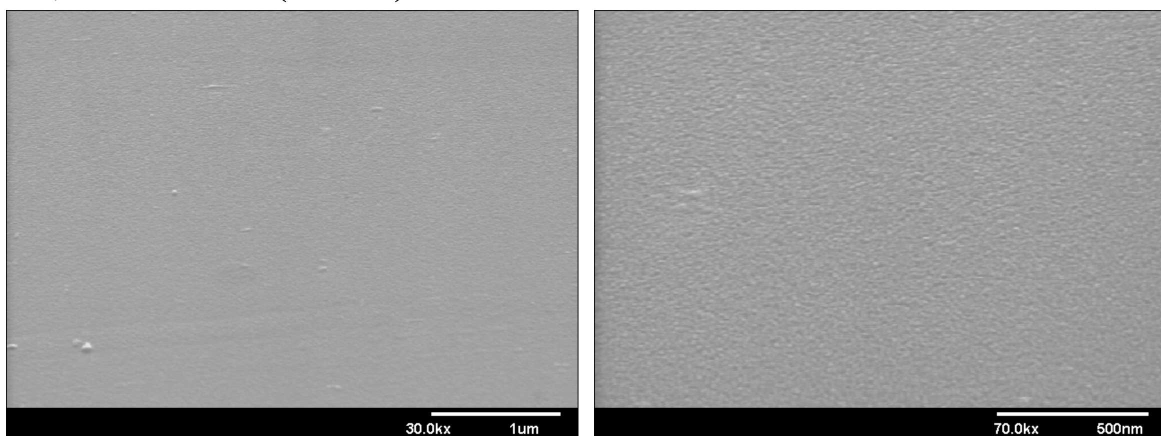
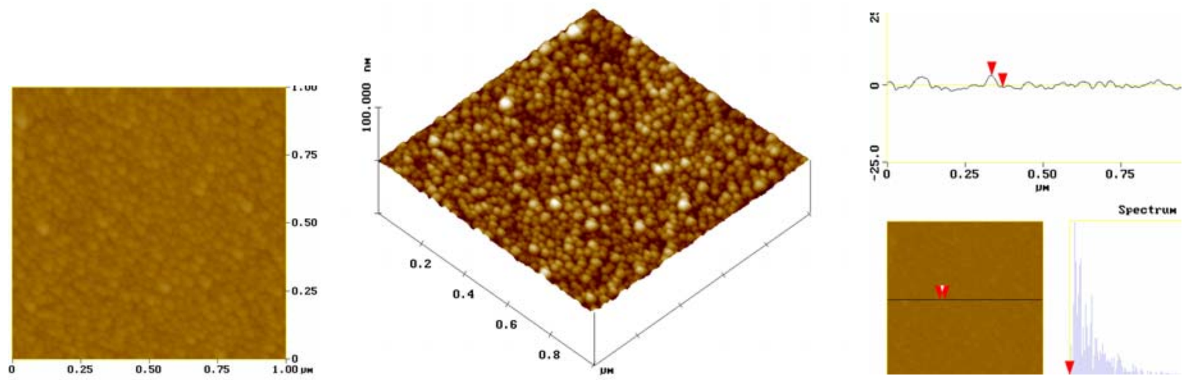
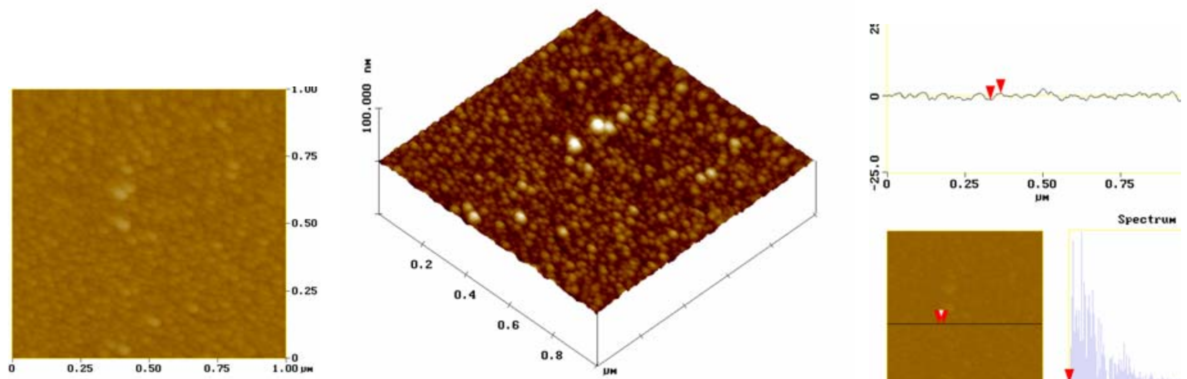


圖 4-6 製程 A 無緩衝層試件(1、2、3) SEM 圖面(30、70 kx)

A1、550℃ H_2:100 (Ni 1 nm)；Rms 0.866 nm



A2、550℃ H_2:100 (Ni 5 nm)；Rms 0.904 nm



A3、550℃ H_2:100 (Ni 7 nm)；Rms 0.700 nm

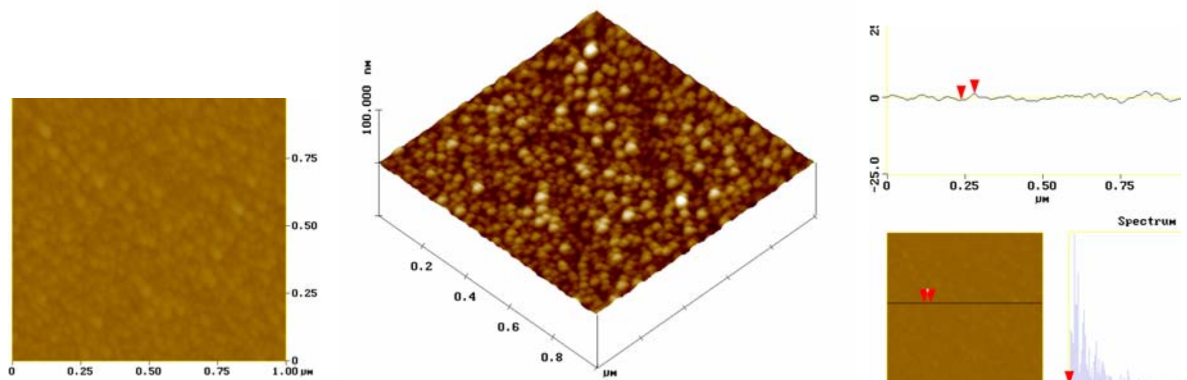
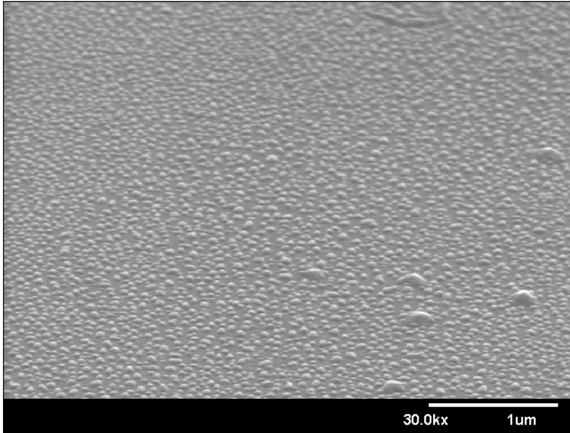
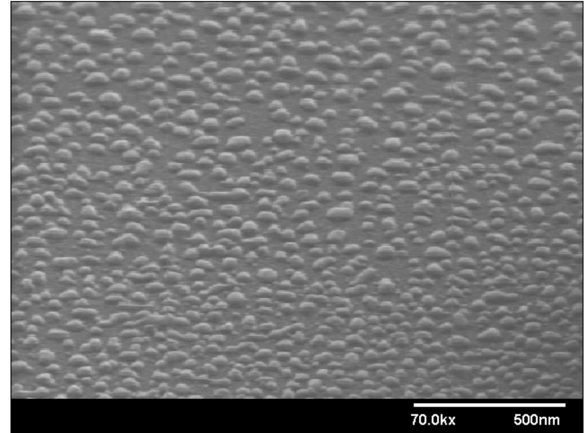


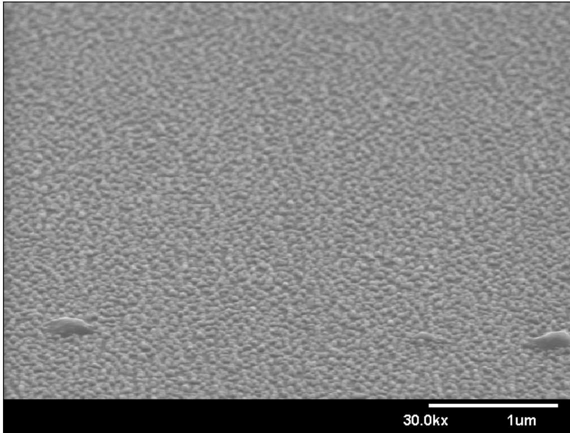
圖 4-7 製程 A 無緩衝層試件(1、2、3) AFM 圖面

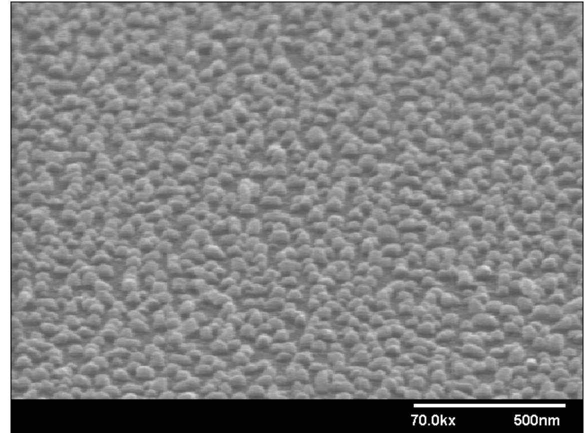
B1、550℃ H_2:200 (Ni 1 nm)



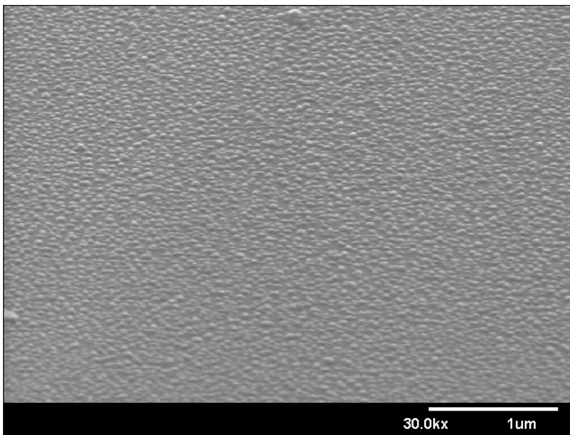


B2、550℃ H_2:200 (Ni 5 nm)





B3、550℃ H_2:200 (Ni 7 nm)



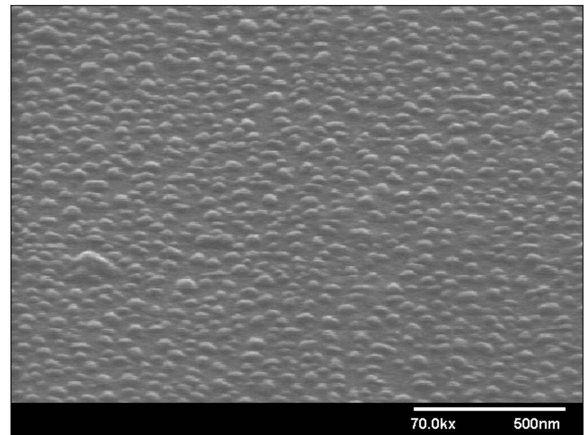
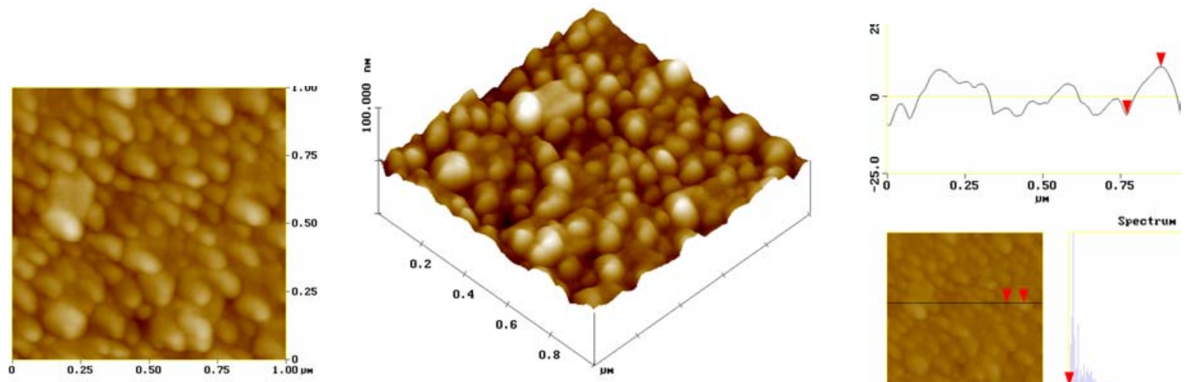
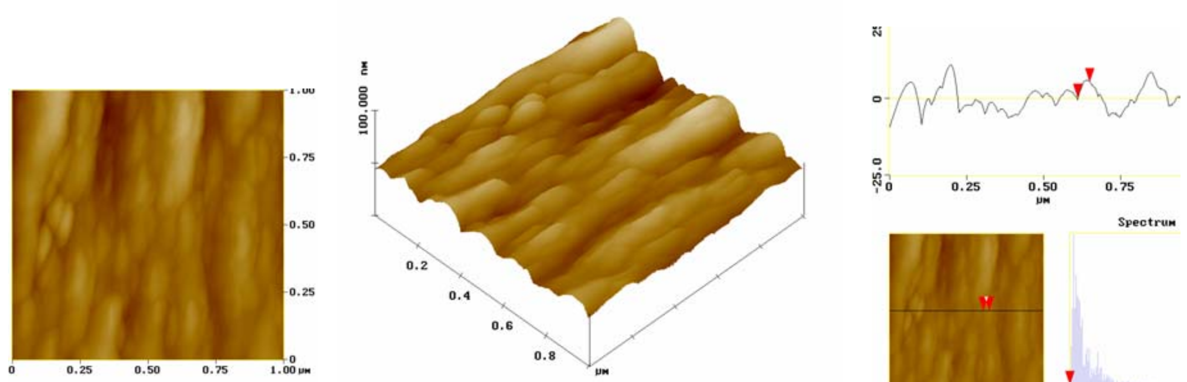


圖 4-8 製程 B 無緩衝層試件(1、2、3) SEM 圖面(30、70 kx)

B1、550℃ H_2:200 (Ni 1 nm)；Rms 3.433 nm



B2、550℃ H_2:200 (Ni 5 nm)；Rms 5.438 nm



B3、550℃ H_2:200 (Ni 7 nm)；Rms 3.274 nm

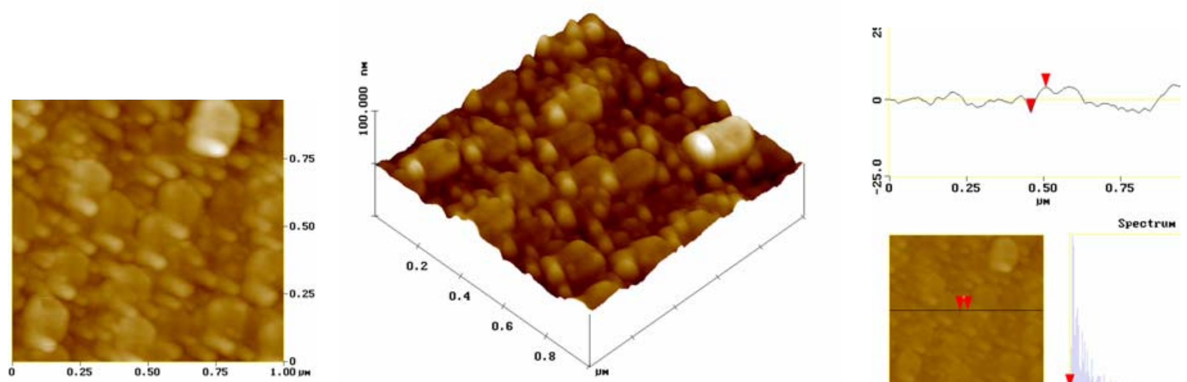


圖 4-9 製程 B 無緩衝層試件(1、2、3) AFM 圖面